

METAL ION REDUCTION IN NOVOLAK RESINS**Abstract of the Invention**

The present invention provides methods for producing water insoluble, aqueous alkali soluble novolak resins having a very low level of metal ions, utilizing treated ion exchange resins. A method is also provided for producing photoresist composition having a very low level of metal ions from such novolak resins and for producing semiconductor devices using such photoresist compositions.

This Sheet Has Been Replaced

